



PRESS RELEASE

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PICOSUN AND TOHOKU UNIVERSITY ANNOUNCE THEIR CO-OPERATION IN ATOMIC LAYER DEPOSITION

HELSINKI, Finland and SENDAI, Japan – April 17, 2008 - Picosun Oy, Finland and Tohoku University, Japan announce their collaboration in the field of Atomic Layer Deposition (ALD).

"We are proud that Tohoku University has joined our ALD network by choosing Picosun as their ALD tool provider. Our co-operation will lead to new results in implementation of ALD in nanotechnology applications and further strengthen the market position of our SUNALE™ ALD process tools in Japan", stated Juhana Kostamo, Managing Director of Picosun Oy.

"Picosun possesses 30 years experience in ALD technology. Picosun's ALD tools are technologically-sophisticated and Japanese customers are now convinced that Picosun's ALD tools are the best in the market. More and more customers in need of high-quality ALD tools both in industry and academia are now choosing Picosun as their partners. We are proud of distributing Picosun's ALD tools in Japan", stated Hiroshi Sato, General Manager of Altech Co., Ltd.

Picosun's SUNALE™ ALD reactor
in use at Tohoku University's
Quantum and Materials
Science Laboratory in Japan.



Professor Makoto Kohda
of Tohoku University

"In semiconductor spintronics, gate controlled spin manipulation and its device application are one of the important technologies for realizing spin based functional devices. Al₂O₃ formed by SUNALE™ ALD R-75BE reactor system enables us to realize pin-hole free and thinner gate insulator on top of semiconductor two dimensional electron gas and shows excellent device characteristics", stated Prof. Makoto Kohda of Tohoku University.

Tohoku University was founded in 1903 as the third Imperial University in Japan, following Tokyo and Kyoto. Its Graduate School of Engineering dates its roots back to the early 1920s. Professor Junsaku Nitta's Quantum and Materials Science laboratory studies a new paradigm, electronics based on the spin degrees of freedom of the electron requiring a way of controlling electron spins in semiconductor channels by using gate bias voltage.

Altech, since its foundation in 1976, has been operating successfully as a leading trading company for specialized industrial machineries. In the 30 years of operation, Altech has tried their best to provide globally acknowledged top-class machinery to top-class clients. Altech's current range of supply includes nano technology related equipments, covering the field of life science to semiconductor electronics.

Picosun is an international equipment manufacturer with world-wide sales and service organization. Picosun develops and manufactures Atomic Layer Deposition (ALD) reactors for micro- and nanotechnology applications. Picosun represents continuity to over three decades of ALD reactor manufacturing in Finland. Picosun provides its customers with versatile, reliable and user-friendly ALD process tools, which offer unique scalability from research to production. Picosun is based in Espoo, Finland and has its US headquarters in Detroit, Michigan. SUNALE™ ALD process tools are installed in various universities, research institutes and companies across Europe, USA and Asia. Doctor Tuomo Suntola, inventor of ALD technology, is Chief Scientific Advisor and Member of the Board of Directors of Picosun. Picosun Oy is a part of Stephen Industries Inc Oy.

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